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**In the Abstract:**

Amend the Abstract as follows:

~~A computer architecture~~ Architecture and method ~~for transferring to transfer~~ data in the ~~generating and displaying generation, display or printing~~ [[of]] high edge placement accuracy images having high edge placement accuracy derived from multiply ~~multiple~~ exposures of ~~[[a]] plurality of predefined patterns, each having inherently with~~ lower edge placement accuracy. The edge placement accuracy achieved can far exceed that normally afforded by the pixel size of the image transducer on which is formed the coarse pattern. The procedure starts with ~~A pattern is laid out on a grid finer than, or different from, the grid size defined by the~~ of image transducer pixel size of the image transducer, which is overlaid by ~~[[the]]~~ transducer grid and converted to n different patterns compatible with ~~[[the]]~~ transducer grid. When suitably combined by partial exposures that weight the weighting patterns unevenly, the n patterns generate a viewable or recordable ~~an image with line edge positions that are a fraction (1/(2<sup>n</sup>-1)) of [[the]] transducer grid size. For most picture display applications and for a step-and-repeat lithography application applications, [[the]] pattern stored in [[the]] first memory is displayed or partially exposed once, and [[the]] remaining patterns stored in memory are displayed or partially exposed 2<sup>m-1</sup> times where m is the~~ being copy number of the copy of the pattern. ~~By superimposing~~ Superimposing 2<sup>n</sup>-1 exposures in the time it takes the human eye to scene integration time ~~integrate a scene, [[a]] picture with improved line placement accuracy is perceived. Similarly, superimposing 2<sup>n</sup>-1 partial exposures in photosensitive recording medium will produce an improved recorded image. The present invention is particularly applicable to applications involving the transfer of large amounts of data in a short time interval, such as maskless step and repeat and maskless step and flash lithography.~~